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a. Serial No.	f. Foreign Priority	k. Print Claim(s)	<u>p.</u> PTO-1449
b. Applicant(s)	g. Disclaimer	l. Print Fig.	q. PTOL-85b
c. Continuing Data	h. Microfiche Appendix	m. Searched Column	r. Abstract
d. PCT	i. Title	n. PTO-270/328	s. Sheets/Figs
e. Domestic Priority	j. Claims Allowed	o. PTO-892	t. Other

- a. Page Missing
- b. Text Continuity
- c. Holes through Data
- d. Other Missing Text
- e. Illegible Text
- f. Duplicate Text
- g. Brief Description
- h. Sequence Listing
- i. Appendix
- j. Amendments
- k. Other

- a. Claim(s) Missing
- b. Improper Dependency
- c. Duplicate Numbers
- d. Incorrect Numbering
- e. Index Disagrees
- f. Punctuation**
- g. Amendments
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MESSAGE ^①PTO-1449: "Please either initial or line through citations". Copies attached. (7 pages)

② Claim #7 is missing the period.
Please supply.

Thank You,
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RESPONSE ^① initial copy provided

② claim 7 does not appear to be missing a period
See amndt. dated 12/12/03 which is last amendment to
claims. (see attached)

initials CF

1 6. (original) The method of claim 2, wherein the conductive layer further comprises a metal
2 deposited onto the conductive polymer.

1 7. (currently amended) The method of claim 1, wherein the selected portions of the
2 conductive layer on the top surface of the Ferroelectric ferroelectric material are selected
3 by patterning the conductive layer on the top surface of the Ferroelectric ferroelectric
4 material.

1 8. (currently amended) The method of claim 7, wherein the conductive layer on the top
2 surface of the Ferroelectric ferroelectric material is patterned by:
3 a. forming a mask over the conductive layer on the top surface of the Ferroelectric
4 ferroelectric material;
5 b. selectively removing the exposed portion of the conductive layer on the top
6 surface of the Ferroelectric ferroelectric material; and
7 c. removing the mask.

1 9. (original) The method of claim 8, wherein the mask is formed from a photo-resist.

1 10. (currently amended) The method of claim 9, wherein the mask is formed by:
2 a. depositing the photo-resist on the conductive layer on the top surface of the
3 Ferroelectric ferroelectric material;
4 b. exposing areas of the photo-resist with a light source according to a predetermined
5 pattern; and
6 c. developing the photo-resist to remove the unexposed portions of the photo-resist.

1 11. (currently amended) The method of claim 1, further comprising the steps of placing the
2 conductive layer on the top surface of the Ferroelectric ferroelectric material and the
3 conductive layer on the bottom surface of the Ferroelectric ferroelectric material in
4 electrical communication.

1 12. (currently amended) The method of claim 11, wherein the step of placing the conductive
2 layer on the top surface of the Ferroelectric ferroelectric material and the conductive layer

FORM PTO-1449 (Modified)		JUL 14 2003		U.S. Department of Commerce Patent and Trademark Office		Attorney Docket No.: SLM-06100		Serial No.: 10/047,550	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use Several Sheets If Necessary)						Applicants: Gregory D. Miller et al			
(37 CFR § 1.98(b))						Filing Date: January 15, 2002		Group Art Unit-2881 1731	

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	AI						

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U.S. Department of Commerce
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Attorney Docket No.: SLM-06100

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Applicants: Gregory D. Miller et al

(37 CFR § 1.98(b))

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Group Art Unit: 2881-1731

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				Filing Date: January 15, 2002		Group Art Unit: 2801 1731		
(37 CFR § 1.98(b))								
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(37 CFR § 1.98(b))						Filing Date: January 15, 2002		Group Art Unit: 3884 1731	
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use Several Sheets If Necessary)				Applicants: Gregory D. Miller et al	
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